



## The Applications of Plasma Techniques

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Deadline for manuscript  
submissions:

**closed (30 June 2020)**

### Message from the Guest Editor

Dear Colleagues,

This Special Issue of the journal Applied Sciences is intended to provide a description of devices and processes related to plasma applications in the broad sense. Plasma is called the fourth state of matter because its properties differ significantly from those of gas. Plasma can be defined as a conductive medium generated by the ionization of gas. Thus, it occurs as a mixture of photons, electrons, and ions, but it can also contain neutral atoms and molecules. The concept of plasma includes media with very different properties. Densities and kinetic energies of plasma components differ for various types of plasma by several or even more orders of magnitude. Hence, plasmas can have very different applications. Readers interested in this modern field of science and technology are invited to enjoy this collection of articles, which will certainly excite the curiosity of both scientists and engineers interested in plasma applications. Moreover, the solutions presented may encourage entrepreneurs to implement them. I wish you a pleasant reading.





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## Message from the Editor-in-Chief

As the world of science becomes ever more specialized, researchers may lose themselves in the deep forest of the ever increasing number of subfields being created. This open access journal Applied Sciences has been started to link these subfields, so researchers can cut through the forest and see the surrounding, or quite distant fields and subfields to help develop his/her own research even further with the aid of this multi-dimensional network.

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